

CSE 560  
Computer Systems Architecture

Technology

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### Survey: What is Moore's Law?

#### What does Moore's Law state?

- A. The length of a transistor halves every 2 years.
- B. The number of transistors on a chip will double every 2 years.
- C. The frequency of a processor will double every 2 years.
- D. The number of instructions a CPU can process will double every 2 years.



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### Technology Unit Overview

#### • Technology basis

- Transistors
- Transistor scaling (Moore's Law)

#### • The metrics

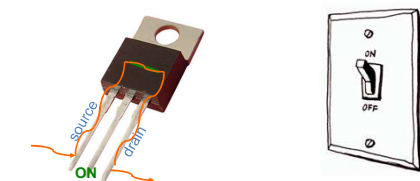
- Cost
- Transistor speed
- Power
- Reliability

How do the metrics change with transistor scaling?

How do these changes affect the job of a computer architect?

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## The Transistor

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### Technology Generations

**1950-1959** Vacuum Tubes

**1960-1968** Transistors

**1969-1977** Integrated Circuit (multiple transistors on chip)

**1978-1999** LSI & VLSI (10Ks & 100Ks transistors on chip)

**2000-20xx** VLSI (millions, now billions transistors on chip)



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## The Silicon in Silicon Valley

**Off**

**N-Type Silicon:** negative free-carriers (free electrons)  
**P-Type Silicon:** positive free-carriers (holes)

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## CMOS: Semiconductor Technology

**On**

**P-Transistor:** negative charge on gate closes channel, connecting source & drain  
**(N-Transistor works the opposite way)**  
 Complementary MOS (CMOS) Technology: uses p & n transistors

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## Transistor Scaling

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## Enter Gordon Moore

The complexity for minimum component costs has increased at a rate of roughly a factor of two per year.... Certainly over the short term this rate can be expected to continue, if not to increase. Over the longer term, the rate of increase is a bit more uncertain, although there is no reason to believe it will not remain nearly constant for at least 10 years. That means by 1975, the number of components per integrated circuit for minimum cost will be 65,000. I believe that such a large circuit can be built on a single wafer.

(From the original 1965 Moore's Law paper)

*"The number of transistors will double every year", 1965*

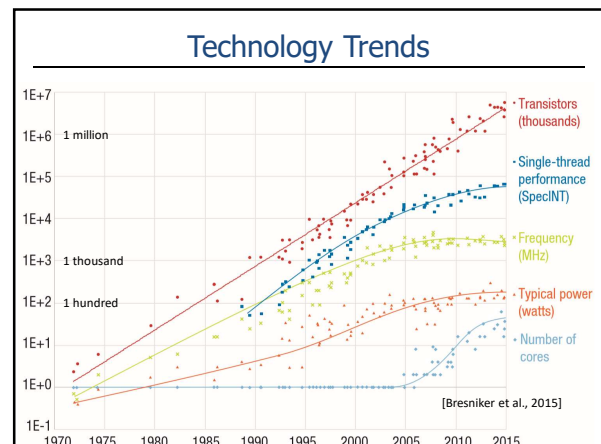
*("...or every two years", 1975)*

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## Moore's Law: Technology Scaling

- Channel length:** characteristic parameter (short → fast)
  - Aka "feature size" or "technology"
  - Currently: 0.007 micron ( $\mu\text{m}$ ), 7 nanometers (nm)
- Moore's Law:** aka "technology scaling"
  - Continued miniaturization ( $\approx$  channel length)
  - + **Improves:** switching **speed**, **power**/transistor, area(**cost**)/transistor
  - **Reduces:** transistor **reliability**

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## Cost

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## Cost

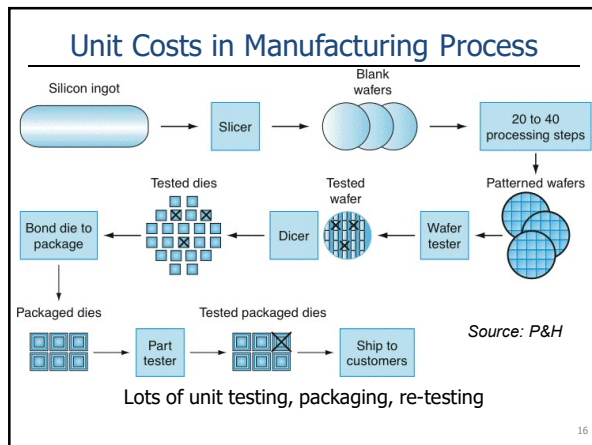
- Metric: \$
- CPU = fraction of cost, so is profit (Intel's, Dell's)

	Desktop	Laptop	Netbook	Phone
\$	\$100-\$300	\$150-\$350	\$50-\$100	\$10-\$20
% of total	10-30%	10-20%	20-30%	20-30%
Other costs	Memory, display, power supply/battery, storage, <b>software</b>			

- We are concerned about *chip cost*
  - Unit cost:** costs to manufacture individual chips
  - Startup cost:** cost to design chip, build the manufacturing facility

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### Unit Cost: Integrated Circuit (IC)

- Cost / wafer is constant, f(wafer size, number of steps)
- Chip (die) cost related to **area**
  - Larger chips → fewer chips/wafer → fewer *working* ones
- Chip cost ~ chip area<sup>α</sup>
  - α = 2 to 3
  - Why? random defects
- Wafer yield:** % wafer that is chips
- Die yield:** % chips that work
  - Yield is increasingly non-binary, fast vs. slow chips

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## Fixed Costs

- For new chip design**
  - Design & verification: ~\$100M (500 person-years @ \$200K per)
  - Amortized over "proliferations", e.g., Xeon/Celeron cache variants
- For new (smaller) technology generation**
  - ~\$3B for a new fab
  - Amortized over multiple designs
  - Amortized by "rent" from companies w/o their own fabs
- Intel's tick-tock** (smaller → better)

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## Transistor Speed

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## Moore's Speed Effect #1: Transistor Speed

**Transistor length:** "process generation"

45nm = transistor gate length

**Shrink** transistor length:

+ ↓ resistance of channel (shorter)

+ ↓ gate/source/drain capacitance

**Result:** switching speed ↑ linearly as gate length ↓

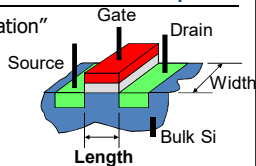
• much of past performance gains

**But** 2<sup>nd</sup>-order effects more complicated

– Process variation across chip increasing

• Some transistors slow, some fast

• Increasingly active research area: dealing with this



Diagrams © Krste Asanovic, MIT

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## Moore's Speed Effect #2: More Transistors

Linear shrink in each of 2 dimensions

• 180 nm, 130 nm, 90 nm, 65 nm, 45 nm, 32 nm, 22 nm, 14 nm, 10 nm, 7 nm ...

• Each generation is a 1.414 linear shrink

• Results in 2x more transistors (1.414 x 1.414)

More transistors → increased performance

• **Job of computer architect:** figure out what to do with the ever-increasing # of transistors

• *Examples:* caches, branch predictors, exploiting parallelism at all levels

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## Moore's Speed Effect #3: Psychological

**Moore's Curve:** common interpretation of Moore's Law

- "CPU performance doubles every 18 months"
- Self fulfilling prophecy: 2x in 18 months is ~1% per week
  - Q: Would you add a feature that improved performance 20% if it would delay the chip 8 months?
- Processors under Moore's Curve (arrive too late) fail spectacularly
  - E.g., Intel's Itanium, Sun's Millennium

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## Power & Energy

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## Power/Energy Increasingly Important

- **Battery life** for mobile devices
  - Laptops, phones, cameras
- **Tolerable temperature** for devices without active cooling
  - Power means temperature, active cooling means **cost**
  - No fan in a cell phone, no market for a hot cell phone
- **Electric bill** for compute/data centers
  - Pay for power twice: once in, once out (to cool)
- **Environmental concerns**
  - "Computers" account for growing fraction of energy consumption

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## Energy & Power

**Energy:** total amount of energy stored/used

- Battery life, electric bill, environmental impact

**Power:** energy per unit time

- Related to "performance" (also a "per unit time" metric)
- Power impacts power supply, cooling needs (cost)
- Peak power vs. average power
  - E.g., camera power "spikes" when you take a picture

Two sources:

- **Dynamic power:** active switching of transistors
- **Static power:** transistors leak even when inactive

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## How to Reduce Dynamic Power

- Target each component:  $P_{\text{dynamic}} \sim N \times C \times V^2 \times f \times A$
- **Reduce number of transistors (N)**
  - Use fewer transistors/gates
- **Reduce capacitance (C)**
  - Smaller transistors (Moore's law)
- **Reduce voltage (V)**
  - Quadratic reduction in energy consumption!
  - But also slows transistors (transistor speed is  $\sim V$ )
- **Reduce frequency (f)**
  - Slow clock frequency – MacBook Air
- **Reduce activity (A)**
  - "Clock gating" disable clocks to unused parts of chip
  - Don't switch gates unnecessarily

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## How to Reduce Static Power

- Target each component:  $P_{\text{static}} \sim N \times V \times e^{-V_t}$
- **Reduce number of transistors (N)**
  - Use fewer transistors/gates
- **Reduce voltage (V)**
  - Linear reduction in static energy consumption
  - But also slows transistors (transistor speed is  $\sim V$ )
- **Disable transistors** (also targets N)
  - "Power gating" disable power to unused parts (long time to power up)
  - Power down units (or entire cores) not being used
- **Dual  $V_t$**  – use a mixture of high and low  $V_t$  transistors (slow for SRAM)
  - Requires extra fabrication steps (cost)
- **Low-leakage transistors**
  - High-K/Metal-Gates in Intel's 45 nm process

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## Moore's Effect on Power

- + **Reduces power/transistor**
  - Reduced sizes and surface areas reduce capacitance (C)
- **Increases power density and total power**
  - By increasing transistors/area and total transistors
  - Faster transistors  $\rightarrow$  higher frequency  $\rightarrow$  more power
  - Hotter transistors leak more (thermal runaway)
- **What to do?** Reduce voltage [486 (5V)  $\rightarrow$  Core2 (1.1V)]
  - +  $\square$  dynamic power quadratically, static power linearly
    - Keeping  $V_t$  the same and reducing frequency (F)
    - Lowering  $V_t$  and increasing leakage exponentially
  - or new techniques like high-K and dual- $V_t$

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## Continuation of Moore's Law

Process Name	P856	P858	Px60	P1262	P1264	P1266	P1268	P1270
1st Production	1997	1999	2001	2003	2005	2007	2009	2011
Process Generation	0.25 $\mu$ m	0.18 $\mu$ m	0.13 $\mu$ m	90 nm	65 nm	45 nm	32 nm	22 nm
Wafer Size (mm)	200	200	200/300	300	300	300	300	300
Inter-connect	Al	Al	Cu	Cu	Cu	Cu	Cu	?
Channel	Si	Si	Si	Strained Si	Strained Si	Strained Si	Strained Si	Strained Si
Gate dielectric	SiO <sub>2</sub>	SiO <sub>2</sub>	SiO <sub>2</sub>	SiO <sub>2</sub>	SiO <sub>2</sub>	High-k	High-k	High-k
Gate electrode	Poly-silicon	Poly-silicon	Poly-silicon	Poly-silicon	Poly-silicon	Metal	Metal	Metal

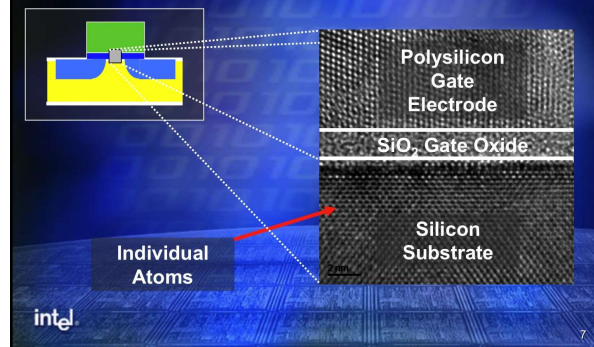
Introduction targeted at this time

Subject to change

Intel found a solution for High-k and metal gate

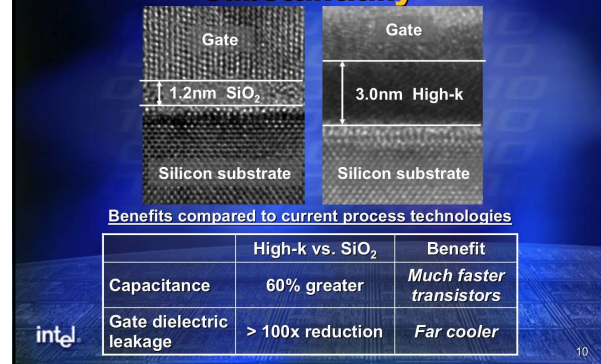
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## Gate dielectric today is only a few molecular layers thick



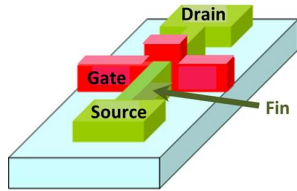
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## High-k Dielectric reduces leakage substantially



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## FinFET



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## Reliability

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## Technology Basis for Reliability

- **Transient faults**
  - A bit "flips" randomly, **temporarily**
  - Cosmic rays etc. (more common at higher altitudes!)
- **Permanent (hard) faults**
  - A gate or memory cell wears out, **breaks and stays broken**
  - Temperature & electromigration slowly deform components
- Solution for both: **redundancy** to detect and tolerate

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## Moore's Bad Effect on Reliability

- **Transient faults:**
    - Small (low charge) transistors are more easily flipped
    - Even low-energy particles can flip a bit now
  - **Permanent faults:**
    - Small transistors and wires deform and break more quickly
    - Higher temperatures accelerate the process
- Wasn't a problem until ~10 years ago (except in satellites)
- Memory (DRAM): these dense, small devices hit first
  - Then on-chip memory (SRAM)
  - Logic is starting to have problems...

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## Moore's Good Effect on Reliability

- Scaling makes devices less reliable
- + Scaling increases device density to enable **redundancy**
- Examples
  - Error correcting code for memory (DRAM),  $\beta$ s (SRAM)
  - Core-level redundancy: paired-execution, hot-spare, etc.
  - Intel's Core i7 (Nehalem) uses 8 transistor SRAM cells
    - Versus the standard 6 transistor cells
- Big open questions
  - Can we protect logic efficiently? (w/o 2-3x overhead)
  - Can architectural techniques help hardware reliability?
  - Can software techniques help?

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## Summary

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# Moore's Law in the Future

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- Won't last forever, approaching physical limits
  - But betting against it has proved foolish in the past
  - Likely to "slow" rather than stop abruptly
- Transistor count will likely continue to scale
  - "Die stacking" is on the cusp of becoming main stream
  - Uses the third dimension to increase transistor count
- But transistor performance scaling?
  - Running into physical limits
  - Example: gate oxide is less than 10 silicon atoms thick!
    - Can't decrease it much further
  - Power is becoming a limiting factor

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# Moore's Law & Chicken Little

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*Appears in the Proceedings of the 27<sup>th</sup> Annual International Symposium on Computer Architecture*

## Clock Rate versus IPC: The End of the Road for Conventional Microarchitectures

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### Abstract

The doubling of microprocessor performance every three years has been the rule of two factors: more transistors per chip and superior scaling of the processor clock with technology generation. Our results show that due to both diminishing improvements in clock rates and poor wire scaling at semiconductor devices shrink, the achievable performance growth of conventional microarchitectures will slow substantially. In this paper, we describe technology-driven models for wire capacitance, wire delay, and microarchitectural component delay. Using the results of these models, we measure the simulated performance—estimating both clock rate and IPC—of an aggressive use of order microarchitectures as it scaled from a 250nm technology to a 35nm technology. We perform this analysis for three clock scaling targets and two microarchitectural scaling strategies: pipeline scale and capacity scaling. We find that the current strategy provides almost no performance improvements of better than 0.25%, which is far worse than the trend. 50-60% to which we have grown transistors in a chip.

the past decade's annualized rate of 50% per year. We find that the rate of clock speed improvement must soon drop to scaling linearly with minimum gate length, between 12% and 17% per year. Compensating for the slower clock growth by increasing sustained IPC proportionally will be difficult. Wire delays will limit the ability of conventional microarchitectures to improve instruction throughput. Microprocessor cores will soon face a new constraint, one in which they are communication bound on the die instead of capacity bound. As feature sizes shrink, and wires become slower relative to logic, the amount of state that can be accessed in a single clock cycle will cease to grow, and will eventually begin to decline. Increases in instruction-level parallelism will be limited by the amount of state reachable in a cycle, not by the number of transistors that can be manufactured on a chip.

For conventional microarchitectures implemented in future

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Compensating for the slower clock growth by increasing sustained IPC proportionally will be difficult. Wire delays will limit the ability of conventional microarchitectures to improve instruction throughput. Microprocessor cores will soon face a new constraint, one in which they are *communication bound* due to the increased *capacity bound*. As feature sizes shrink, and wires become slower relative to logic, the amount of state that can be accessed in a single clock cycle will be limited. This will begin to limit the rate of state transition to decline. Increases in instruction-level parallelism will be limited by the amount of state reachable in a cycle, not by the number of transistors that can be manufactured on a chip.

For conventional microarchitectures implemented in future

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[illegible]

*Appears in the Proceedings of the 38<sup>th</sup> International Symposium on Computer Architecture (ISCA '10)*

**Dark Silicon and the End of Multicore Scaling**

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<sup>1</sup>University of Washington <sup>2</sup>University of Wisconsin-Madison  
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## ABSTRACT

**ABSTRACT** Process manufacturing has increased core counts to exploit Moore's Law scaling, rather than focusing on single-core performance. The failure of Dennard scaling, to which the shift to multi-core is partially a response, has been well documented. However, single- and multi-processor scaling has not been curtailed. This paper models multi-core scaling levels by combining device scaling, single-core scaling, and multi-core scaling to measure the spatial potential for scaling of parallel processing architectures. Technology generation scaling is used for parallel processing architectures, while multi-core scaling is used for multi-processor scaling. To model multi-processor scaling, we use both the ITRES processor model and a set of more conservative device scaling parameters. To model single-core scaling, we combine measurements from over 150 processors with a technology generation scaling model. We compare the performance. Finally, to model multi-core scaling, we build a detailed performance model of approx-based performance and known-based core power. The multi-core designs we study include single-core, multi-core, and multi-processor designs. We compare these organizations with symmetric, asymmetric, dynamic, and complex topologies. The study shows that regardless of chip organizations and topology, multi-core scaling is power limited to a degree not previously appreciated. Scaling of multi-core scaling is limited (just one from now), 21% of a fixed-size chip must be powered off, and at 8 nm, this number grows to more than 50%. Therefore, about 1/15th on-chip storage is possible across commonly used technology nodes, leaving a nearly 25-fold gap from a target of doubled performance per generation.

[illegible]

Now, however, researchers fear that this extraordinary acceleration is about to meet its limits. The problem isn't that they cannot squeeze more transistors onto the chips — they surely can — but instead, like a city that cannot provide electricity for its entire streetlight system, that all the transistors could require too much economically. They could overheat,

...all going to die' papers," Dr. Patte  
...to innovate, since we don't want to

"It's one of those 'If we don't innovate, we're all going to die' papers," Dr. Patterson said in an e-mail. "I'm pretty sure it means we need to innovate, since we don't want to die!"

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## Summary of Device Scaling

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- + Reduces unit cost
  - But increases startup cost
- + Increases performance
  - Reduces transistor/wire delay
  - Gives us more transistors with which to increase performance
- + Reduces local power consumption
  - Quickly undone by increased integration, frequency
  - Aggravates power-density and temperature problems
- Aggravates reliability problem
  - + But gives us the transistors to solve it via redundancy

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